



## PATENT ABSTRACTS OF JAPAN

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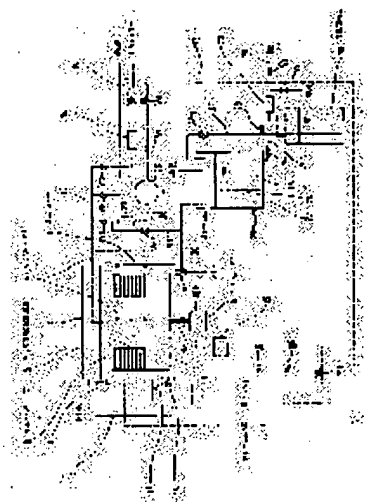
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## (54) CLEANING AND CLEANING APPARATUS

## (57) Abstract:

PURPOSE: To effectively remove a fine dust particle adhered to an object to be cleaned due to static electricity by a method wherein the object to be cleaned is cleaned repeatedly by alternately using alcohol and pure water.

CONSTITUTION: A lid 2 of a chamber 1 is opened; a wafer carrier 8 is housed inside a carrier-housing jig 5; after that, the lid 2 is closed. Then, an exhaust damper 11 is closed; a rotary plate 3 is turned by using in air motor 4; when the preset number of revolutions is reached, alcohol 18 and pure water are sprayed alternately from a shower nozzle 6; while this operation is repeated, the wafer carrier 8 is cleaned by a collision with a sprayed mist particle due to a turning operation and an action of a centrifugal force. By a multiplier effect of an action to remove electricity due to a cleaning operation by using alcohol, a hydrophile substitution action and a subsequent cleaning effect by using pure water, a fine dust particle adhered to an object to be cleaned due to static electricity can be effectively removed.



## LEGAL STATUS

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